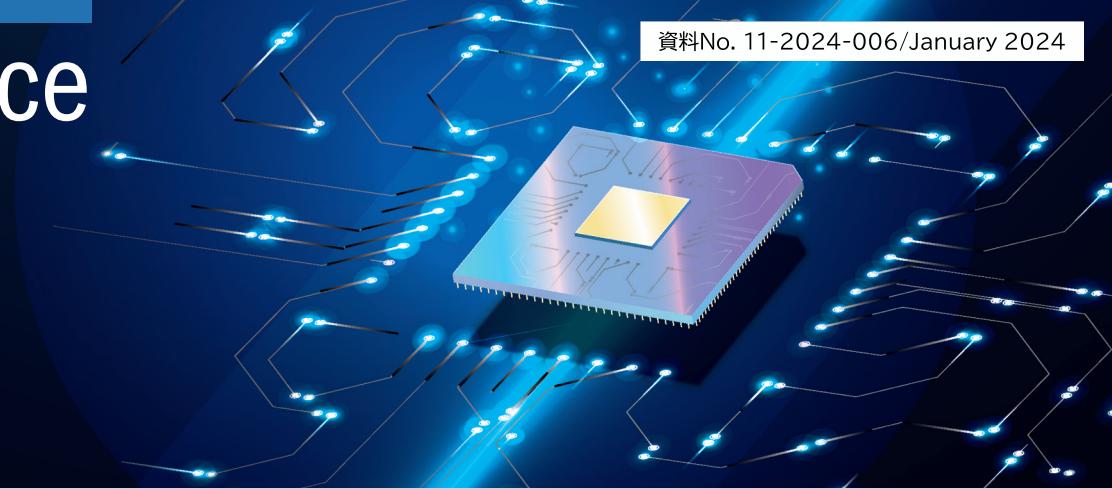


半導体



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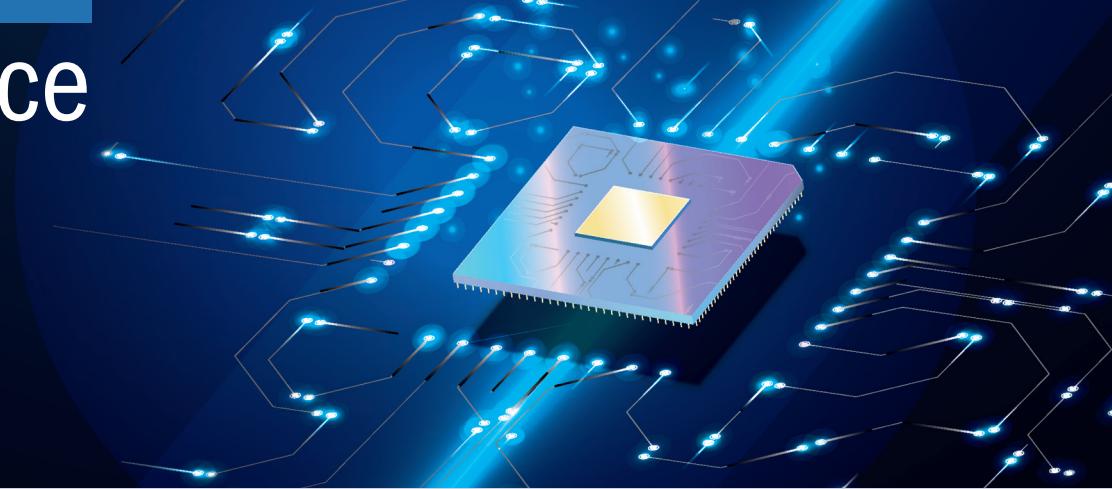
半導体の主な内容:

- NANDフラッシュ
- GaN
- プラズマ
- メモリ
- CMOS
- シリコン
- エッチング
- エピタキシー
- グラフェン
- ナノワイヤ
- 電界
- 走査型電子顕微鏡
- DRAM
- MEMS
- 人工知能
- 薄膜
- FinFET
- 抵抗スイッチング
- 量子回路

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半導体

世界でトップレベルの半導体企業による研究を特集

- Precision of bit slicing with in-memory computing based on analog phase-change memory crossbars
IBM Research Europe, Switzerland and IBM Research Almaden, USA
- Scaling behavior of ferroelectric FET with reduction in number of domains in ferroelectric layer
Applied Materials Inc, United States
- Time-resolved measurement of radical populations in extreme-ultraviolet-light-induced hydrogen plasma
Samsung Electronics Co., Ltd., Korea
- Cryogenic operation of NanoBridge at 4K for controlling qubit
NanoBridge Semiconductor, Inc., Japan
- Low-temperature synthesis of high-quality graphene by controlling the carbon-hydrogen ratio of the precursor
Taiwan Semiconductor Manufacturing Company (TSMC), Taiwan

最近の特別号

- Wide-bandgap semiconductors and applications
Journal of Physics D: Applied Physics
- GaN technology for next generation power devices
Semiconductor Science and Technology™
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Nanotechnology™
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Journal of Physics: Condensed Matter™
- Solid State Devices and Materials
Japanese Journal of Applied Physics
- Semiconductor Wafer Bonding: Science, Technology, and Applications
ECS Journal of Solid State Science and Technology

半導体に関するホットな話題

- Challenges and prospects of nanosized silicon anodes in lithium-ion batteries
- Low-temperature processed beta-phase In_2Se_3 ferroelectric semiconductor thin film transistors
- Raman spectroscopy of colloidal semiconductor nanocrystals
- Recent progress in ferromagnetic semiconductors and spintronics devices
- Electrical conductivity enhancement of transparent silver nanowire films on temperature-sensitive flexible substrates using intense pulsed ion beam
- Tendency of crystal orientation rotation toward stable $\{001\} <100>$ during lateral crystal growth of Si thin film sandwiched by SiO_2
- Fabrication of GaN cantilever on GaN substrate by photo-electrochemical etching

世界トップクラスの革新的な半導体企業が IOPscience を購読しています。

 **MARUZEN-YUSHODO**

【お問合せ・ご注文】

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